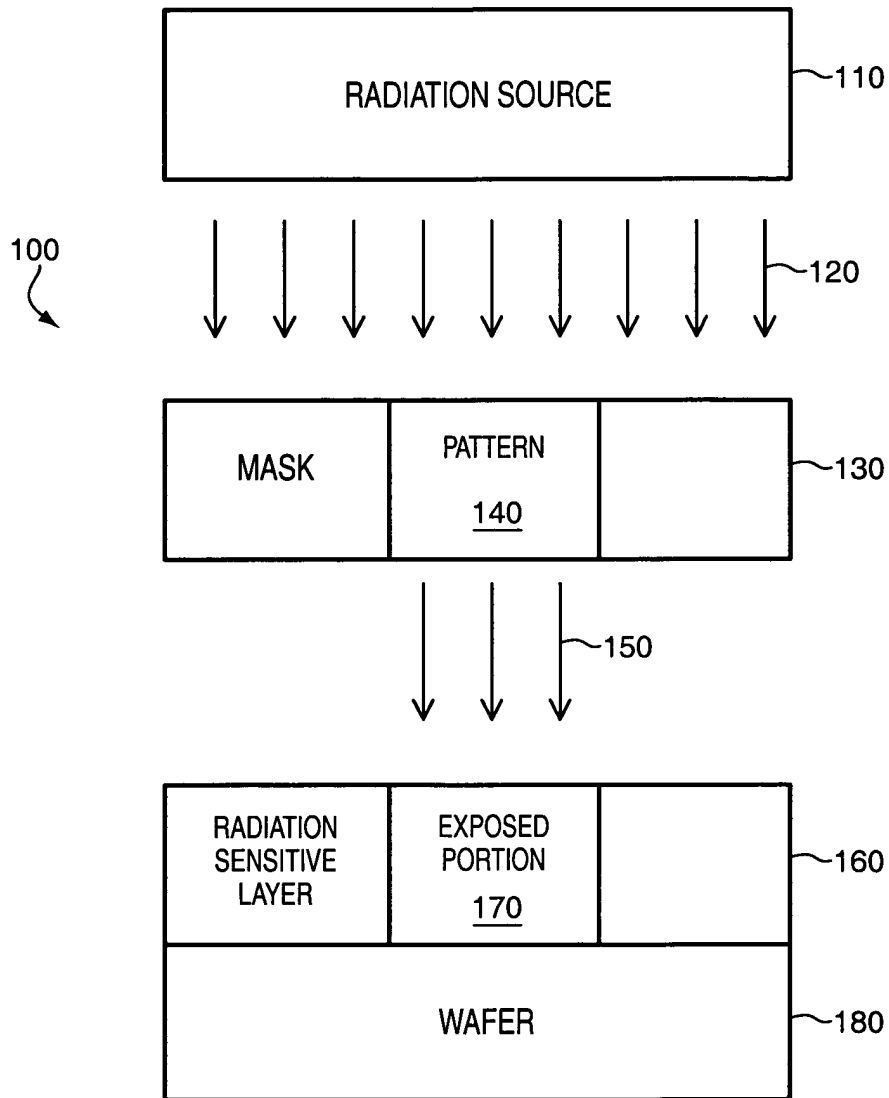




FIG. 1



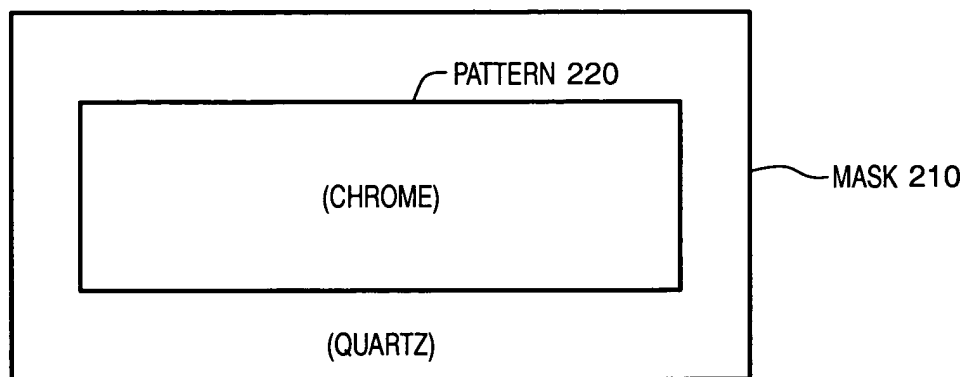


FIG. 2

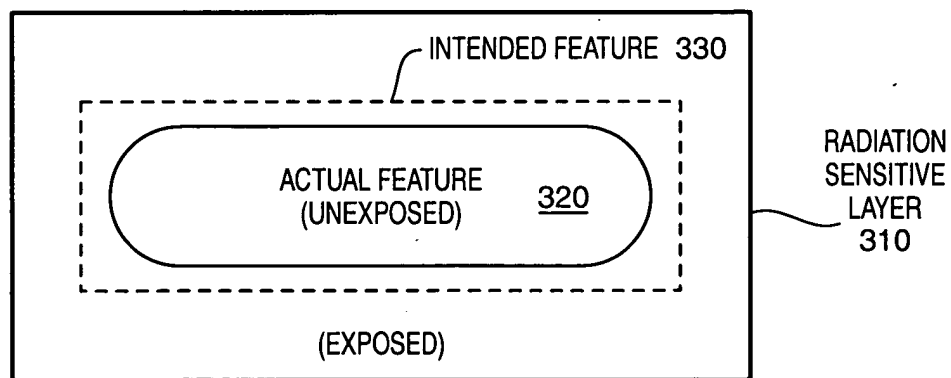


FIG. 3

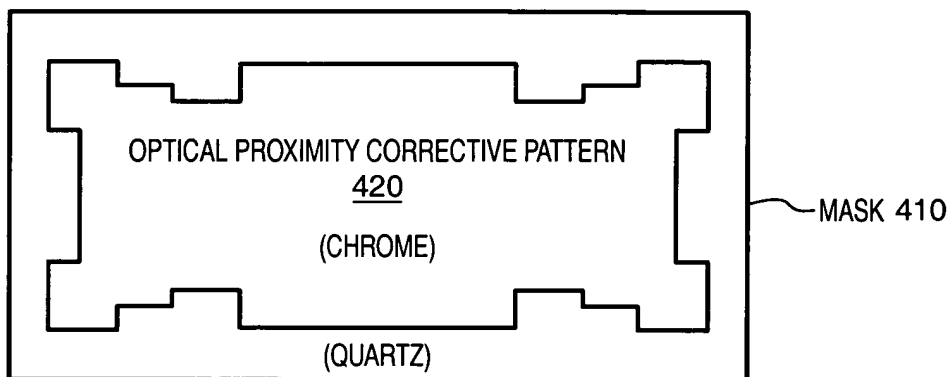


FIG. 4

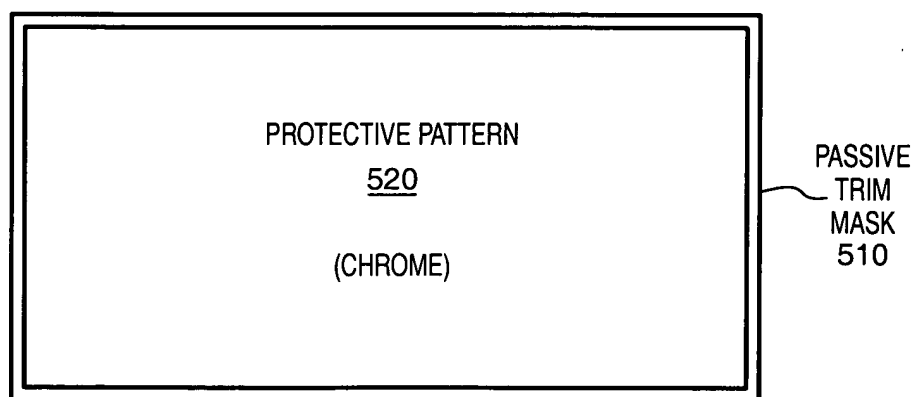
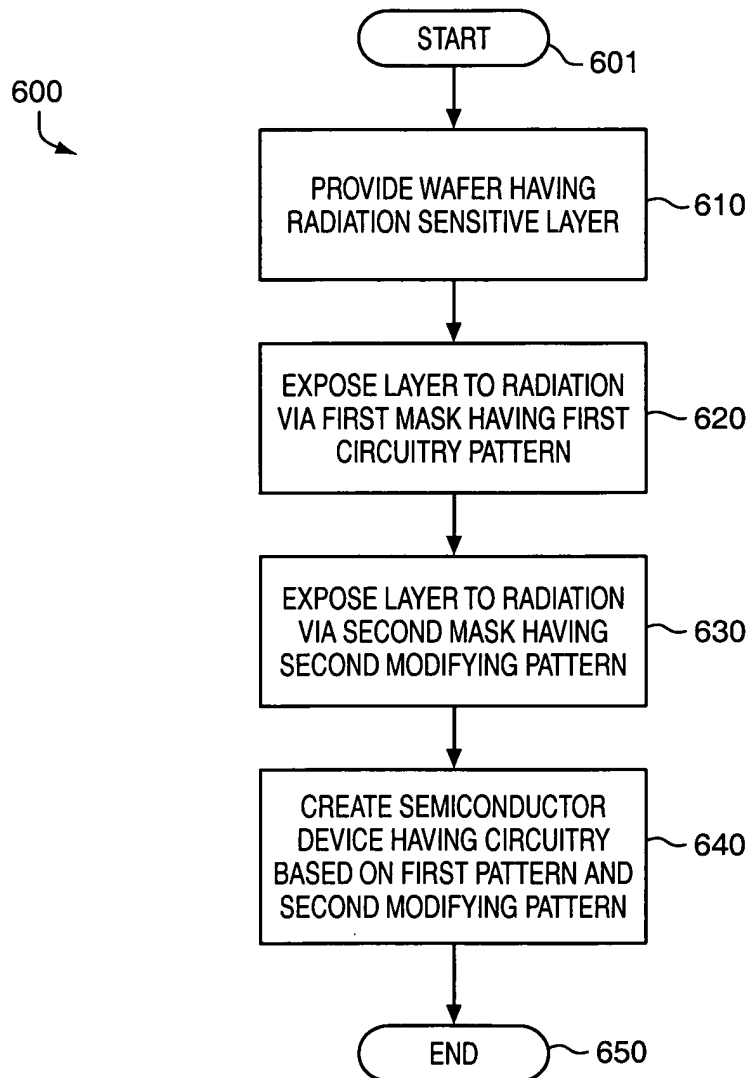


FIG. 5



FIG. 6

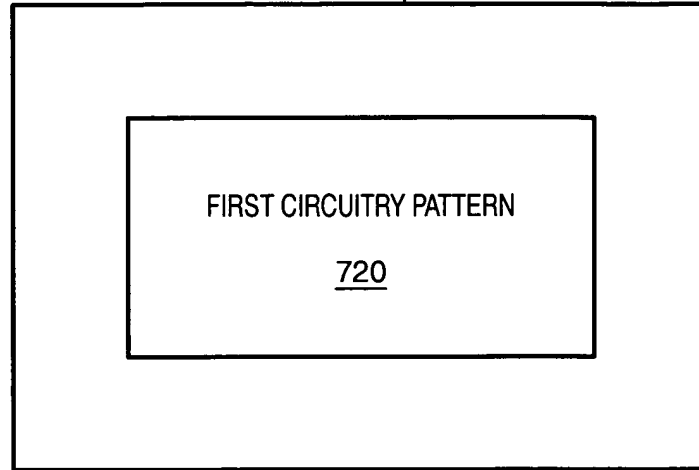




SET OF
MASKS
700



FIRST MASK 710



SECOND MASK 730

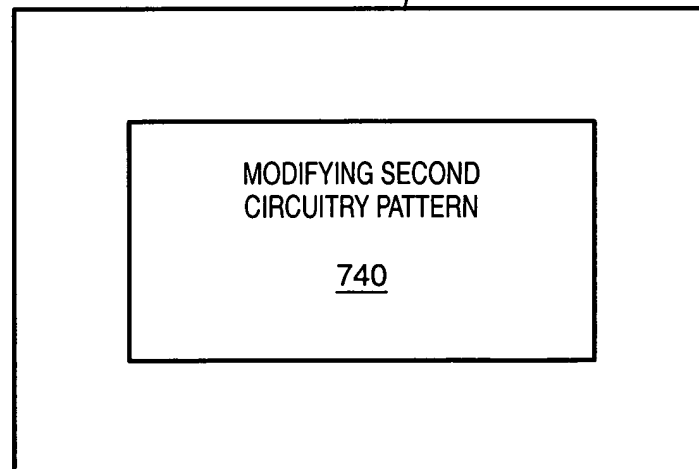
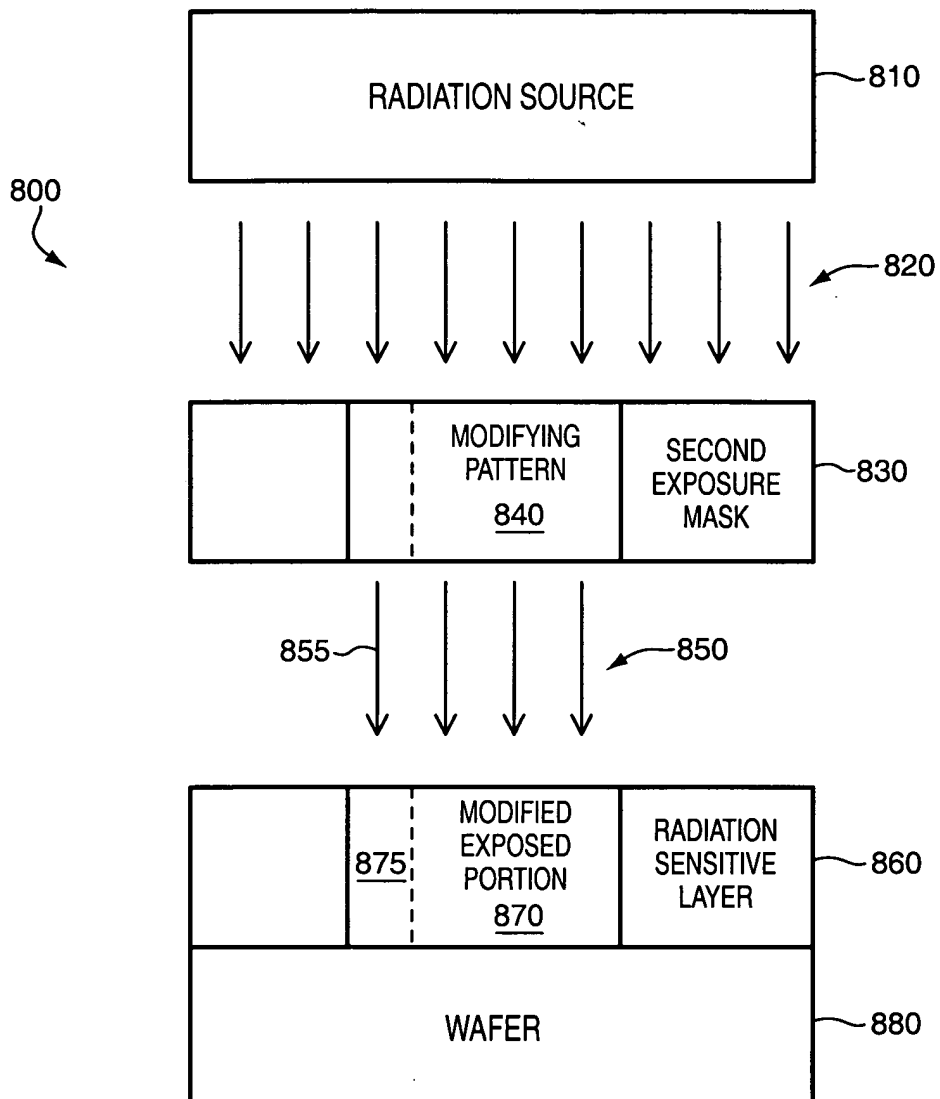


FIG. 7



FIG. 8





7/13

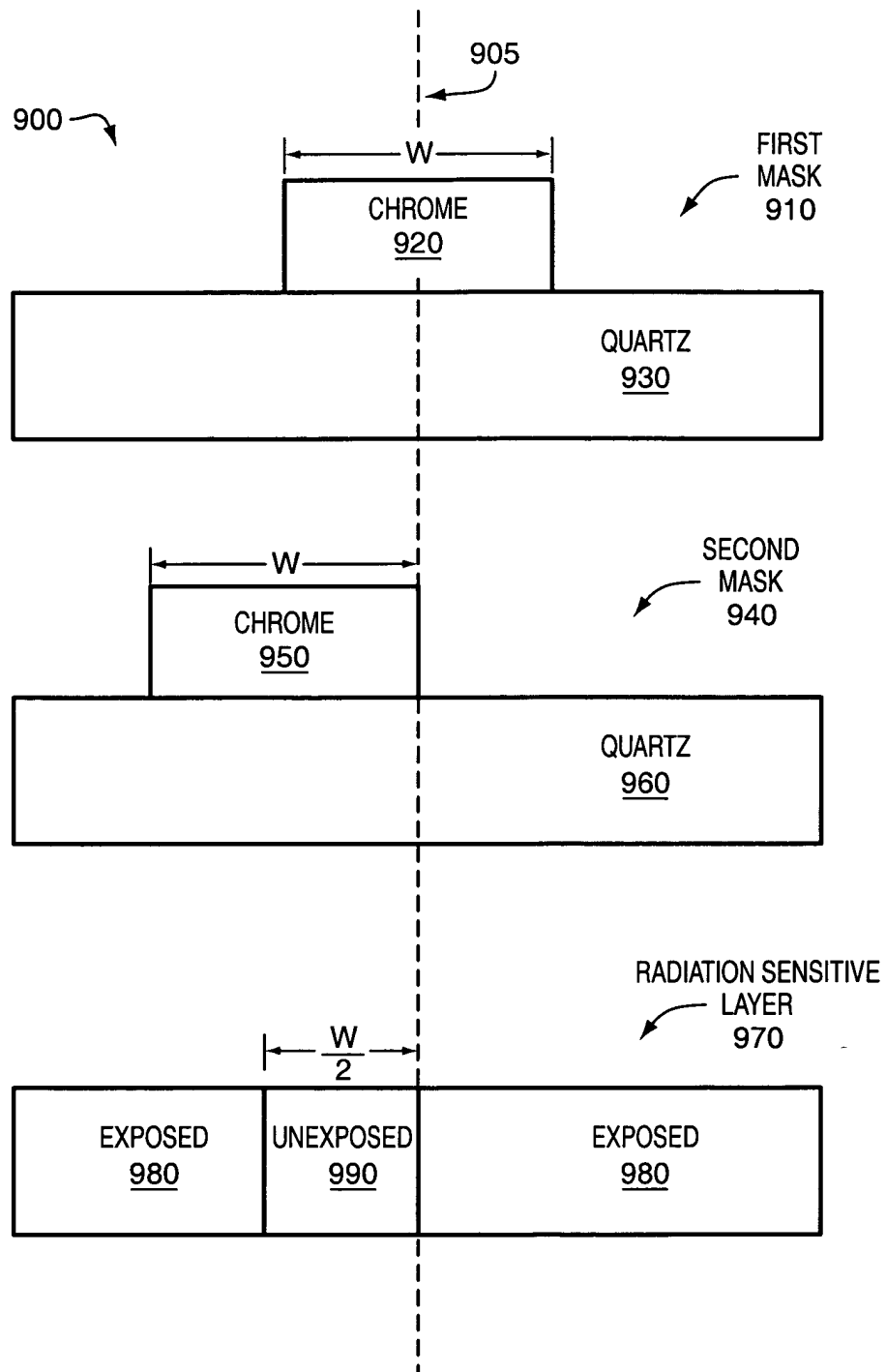


FIG. 9

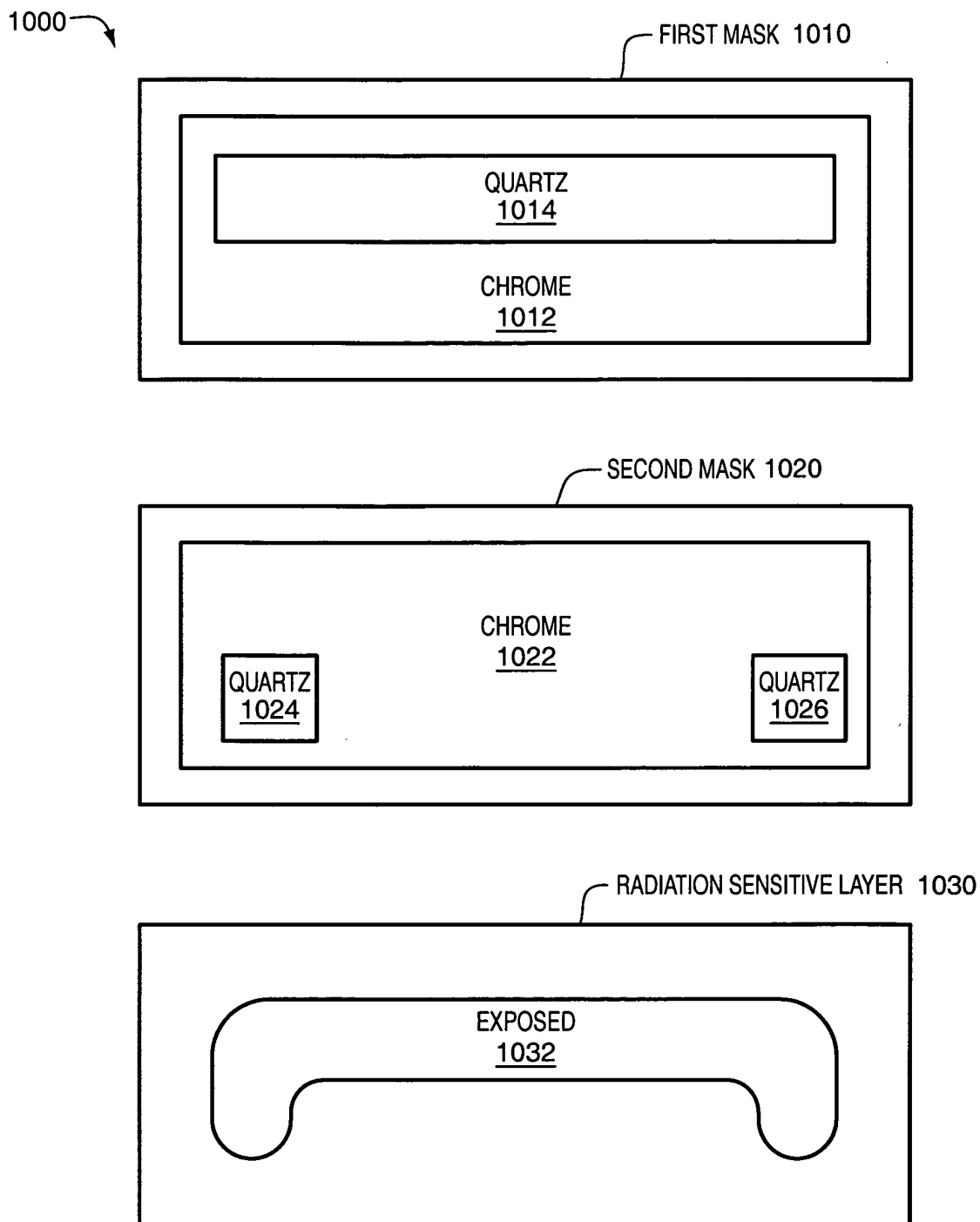
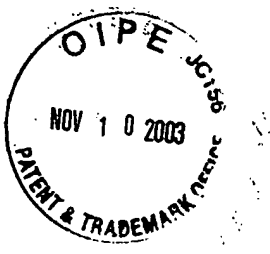


FIG. 10



9/13

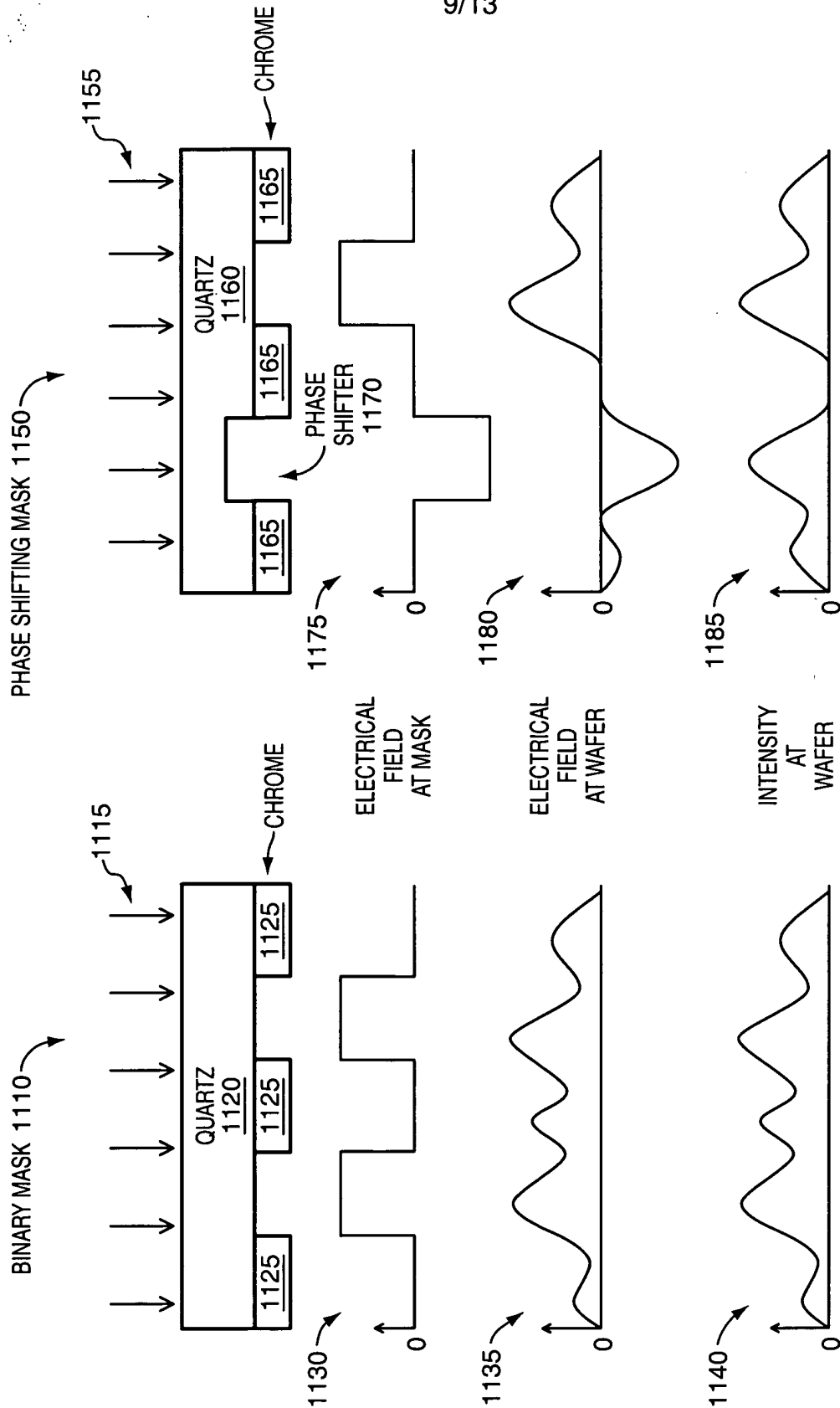


FIG. 11

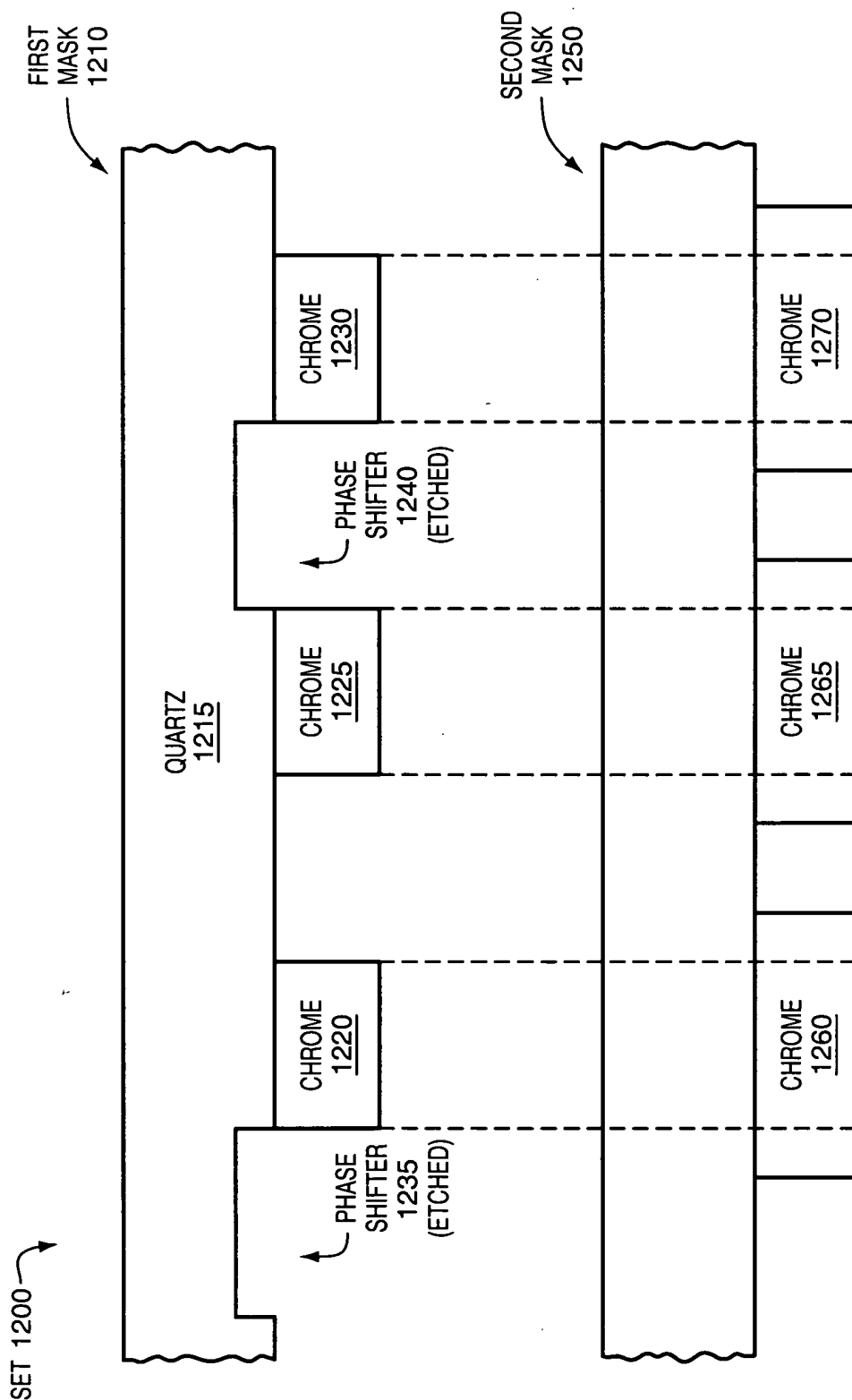


FIG. 12



11/13

SET
1300

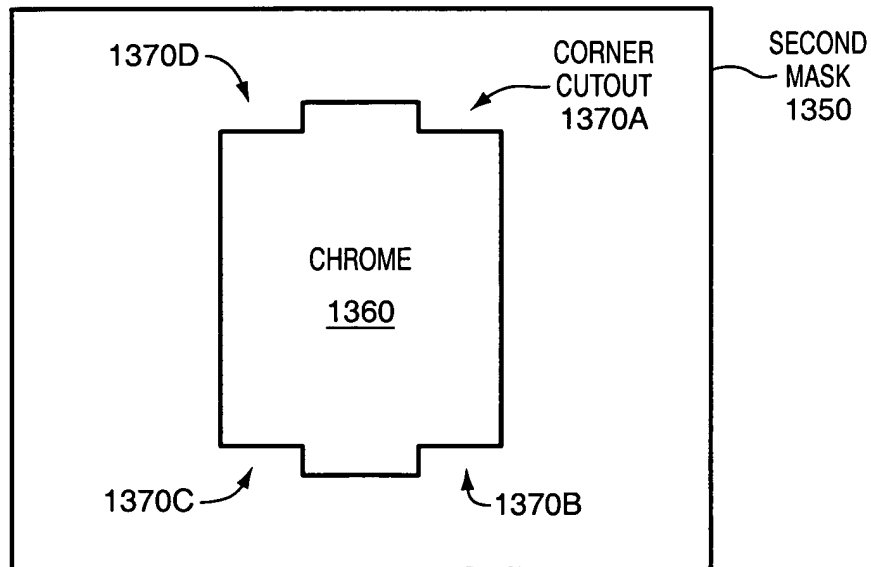
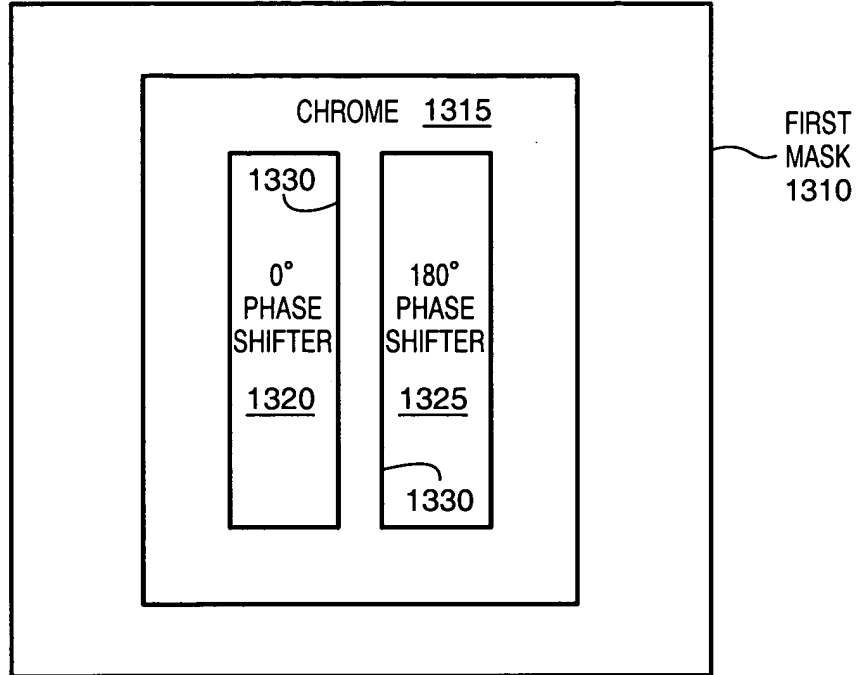


FIG. 13



SET
1400

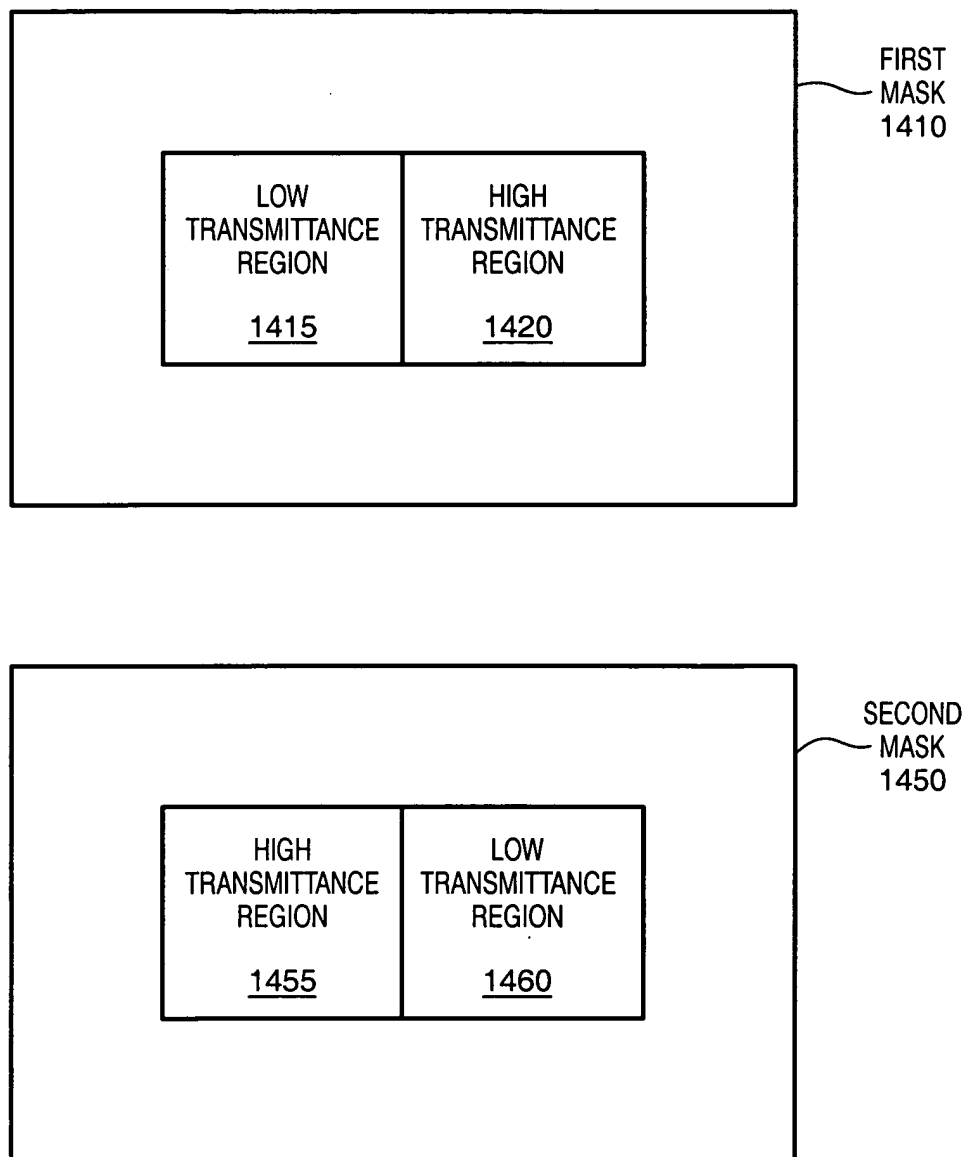


FIG. 14



Title: "An Active Secondary Exposure Mask To Manufacture Integrated Circuits"
Inventors: Fred Chen et al. Application No.: 10/040,772 Attorney Docket No.: 42P11369
Blakely, Sokoloff, Taylor & Zafman 303-740-1980

13/13

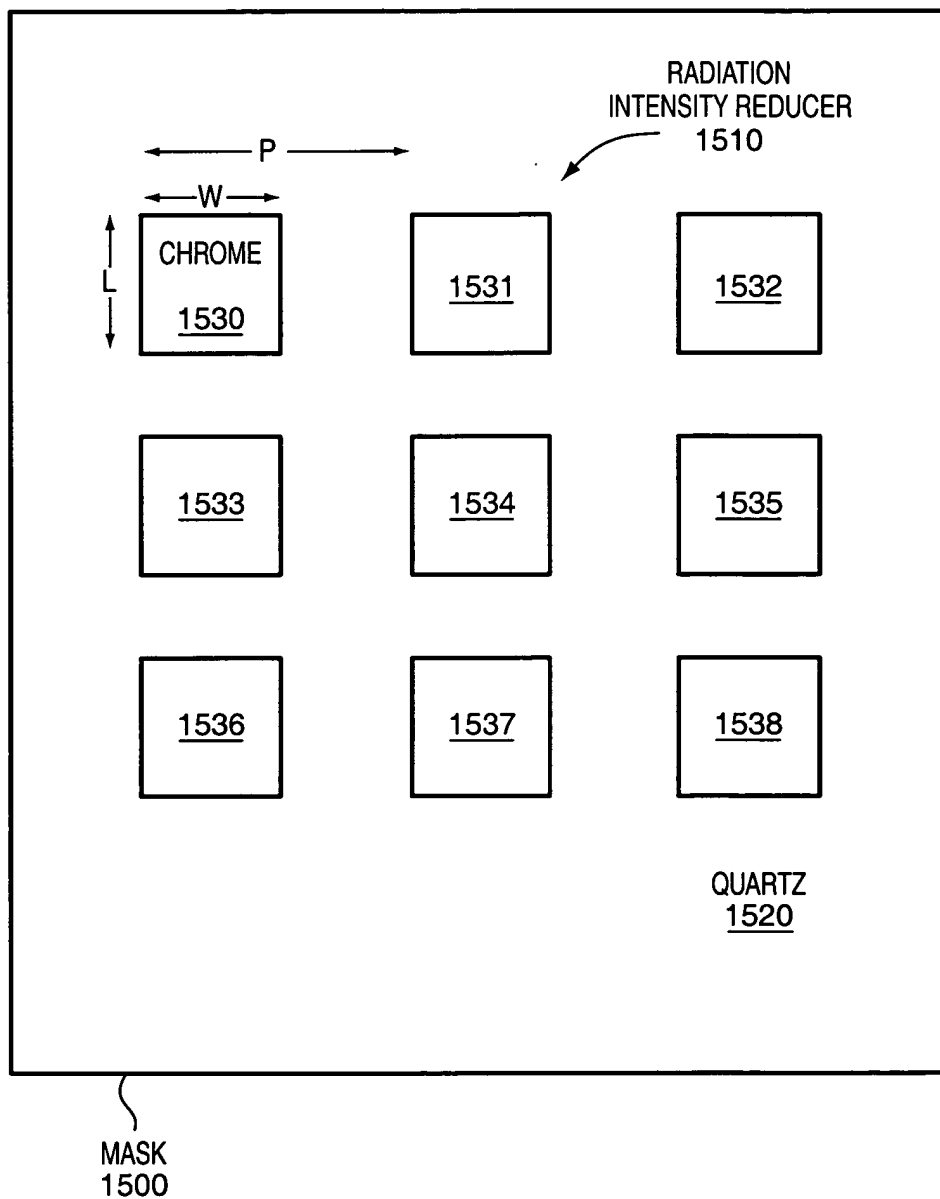


FIG. 15